	Hit s	Search Text	DBs
65	6	or irradiat\$4 or illuminat\$4 or	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
66	18	((EUV or UV or VUV or DUV or X\$2ray) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5 or pattern) near29 strip\$4 near29 (remov\$5))	USPAT; FPRS; EPO; JPO;
67	6	(pattern) near29 strip\$4 near29 (remov\$5)) and ((resist or photoresist) near12 (residu\$3 or	US-PGPUB; USPAT; FPRS; EPO; JPO;